Lu Zheng

List of Publications by Year
in descending order

12	195	1307594 7	1199594 12
papers	citations	h-index	g-index

12	12	12	332
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Phosphorene-directed self-assembly of asymmetric PS-b-PMMA block copolymer for perpendicularly-oriented sub-10 nm PS nanopore arrays. Nanotechnology, 2017, 28, 424001.	2.6	5
2	Facile Fabrication of Anisotropic Colloidal Particles with Controlled Shapes and Shape Dependence of Their Elastic Properties. Particle and Particle Systems Characterization, 2016, 33, 842-850.	2.3	3
3	Quantitative Characterization of Mechanical Property of Annealed Monolayer Colloidal Crystal. Langmuir, 2016, 32, 451-459.	3.5	7
4	Layerâ€byâ€Layer Approach to (2+1)D Photonic Crystal Superlattice with Enhanced Crystalline Integrity. Small, 2015, 11, 4910-4921.	10.0	33
5	Rapid nanostructuration of polymer colloid surfaces by nonsolvent induced phase separation. Journal of Colloid and Interface Science, 2015, 441, 39-45.	9.4	5
6	Monolayer colloidal mask with tunable interstice size for nanosphere lithography. Thin Solid Films, 2013, 544, 83-87.	1.8	3
7	Colloidal monolayer at the air/water interface: Large-area self-assembly and in-situ annealing. Thin Solid Films, 2013, 544, 557-561.	1.8	7
8	Hierarchically ordered arrays based on solvent vapor annealed colloidal monolayers for antireflective coating. Thin Solid Films, 2013, 544, 403-406.	1.8	5
9	Fabrication of volcano-shaped nano-patterned sapphire substrates using colloidal self-assembly and wet chemical etching. Nanotechnology, 2013, 24, 335301.	2.6	24
10	Solventâ€Assisted Interfacial Tension Deformation of Spherical Particles for the Fabrication of Nonâ€Spherical Particle Arrays. Particle and Particle Systems Characterization, 2013, 30, 812-817.	2.3	10
11	Preparation of High-Quality Colloidal Mask for Nanosphere Lithography by a Combination of Air/Water Interface Self-Assembly and Solvent Vapor Annealing. Langmuir, 2012, 28, 12681-12689.	3.5	51
12	Thermal annealing of colloidal monolayer at the air/water interface: a facile approach to transferrable colloidal masks with tunable interstice size for nanosphere lithography. Journal of Materials Chemistry, 2012, 22, 22678.	6.7	42